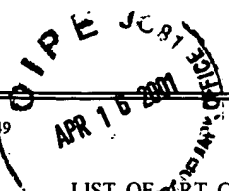


Form PTO-1449		U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI30-052	SERIAL NO. 09/711,587			
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				FILING DATE November 13, 2000		GROUP 2812		
U.S. PATENT DOCUMENTS								
*Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
5	AA	4,957,881	09/90	Crotti				
5	AB	5,157,002	10/92	Moon				
5	AC	5,421,958	06/95	Fathauer et al.				
5	AD	5,427,648	06/95	Pamulapati et al.				
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5	AF	5,518,950	05/96	Ibok et al.				
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5	AL	5,731,214	03/98	Kurihara				
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		Document Number	Date	Country	Class	Subclass	Translation	
							Yes	No
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	AO							
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5	AP		Boswell, E. et al., "Characterization of Porous Silicon Field Emitter Properties", J.Vac.Sci. Technol. B 14(3), May/June 1996, pp. 1895-1898.					
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5	AR		Ko, Y. et al., "Electron Emission and Structure Properties of Cesium Carbon Films Prepared by Negative Carbon Ion Beam", J.Appl. Phys. 82(5), Sept. 1, 1997, pp. 2631-2635.					
5	AS		Lee, J. et al., "Emission Characteristics of Silicon Field Emitter Arrays Fabricated by Spin-On-Glass Etch-back Process", 9 th Internatl. Vacuum Microelectronics Conference, St. Petersburg 1996, pp. 380-383.					
EXAMINER <i>S. Merer</i>				DATE CONSIDERED <i>1-14-03</i>				
<small>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</small>								

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U.S. PATENT DOCUMENTS								
Examiner Initial	Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate		
5	AA	3,814,968	06/74	Nathanson et al.	X			
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5	AE	5,129,850	07/92	Kane et al.				
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		Document Number	Date	Country	Class	Subclass	Translation	
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			pp. 31.6.1 - 31.6.4.					
EXAMINER <div style="font-family: cursive; font-size: 1.2em;">S. meier</div>				DATE CONSIDERED <div style="font-family: cursive; font-size: 1.2em;">1-14-03</div>				
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	Document Number	Date	Country	Class	Subclass	Translation		
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	AM							
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~	AR		ARTICLE: McClatchie, S. et al., "Low Dielectric Constant Flowfill® Technology for IMD Applications", Electrotech Ltd., Bristol, U.K.,					
			undated, 7 pages, <i>Date unknown</i>					
~	AS		ARTICLE: Kiermasz, A. et al., Electrotech Ltd., U.K., "Planarisation for Sub-Micron Devices Utilising a New Chemistry", presented at					
			DUMIC Conference, California, Feb. 1995, 2 pages.					
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			presented at ULSI Conference, Portland, OR, October 1995, pp. 1-7.					
EXAMINER <i>G. Meier</i>				DATE CONSIDERED <i>1-14-03</i>				
<p>*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.</p>								